## ABSTRACT OF THE DISCLOSURE

An onium salt compound having a cation moiety of the following formula (1) is disclosed.

 $(Ar^{2})_{n} A^{+} (Ar^{1})_{m}$  (1)

wherein A represents I or S, m is 1 or 2, n is 0 or 1, x is 1-10, and Ar1 and Ar2 are (substituted) aromatic hydrocarbon group,

10 and P represents -O-SO<sub>2</sub>R, -O-S(O)R, or -SO<sub>2</sub>R, wherein R represents a hydrogen atom, a (substituted) alkyl group, or a (substituted) alicyclic hydrocarbon group. The onium salt compound is suitable as a photoacid generator for photoresists of a positive-tone radiation-sensitive resin composition. The positive-tone radiation-sensitive resin composition containing this compound is useful as a chemically-amplified photoresist exhibiting high resolution at high sensitivity, responsive to various radiations, and having outstanding storage stability.

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